



PTO-1449 Equivalent

Second LIST OF PRIOR ART CITED BY APPLICANT
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GK-OEH-171 / 500814.20073

Applicant(s): **Max Christian SCHUERMANN, et al.**Application No. **10/672,110**Group: **2878**Filed: **September 26, 2003**

Examiner:

U.S. PATENT DOCUMENTS

Exam. Init		Document Number	Date	Name	Class	Sub-Class	Filing Date Appropriate
	AA						
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FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	CLASS	Sub-Class	Translation YES	NO
	AL							
	AM							
	AN							
	AO							
	AP							

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)

OG	AT	XP-001111378 / Research Disclosure, July 2001, 1146 (2 sided page) 447085 "Reflectometer for EUV lithography components"
OG	AU	Microelectronic Engineering 61-62 (2002) pages 145-155, "Characterization of optics and masks for the EUV lithography" Valérie Paret, et al.
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OG	AW	XP-0010183524 / Journal of x-ray Science and Technology 3, (1992) pages 283-299, "A Soft X-Ray/EUV Reflectometer Based in a Laser Produced Plasma Source, E. M. Gullikson, et al.
OG	AX	XP-000497187 / 8257b Journal of Vacuum Science & Technology B 12(1994) Nov/Dec, No. New York, NY, US, pages 3826-3832, "Multilayer facilities required for extreme-ultraviolet lithography, D.L. Windt, et al.
OG	AY	Nuclear Instruments and Methods in Physics Research A 359 (1995) pages 151-154, Synchrotron radiation soft X-ray reflectometer and its physics results, Cui Mingqi, et al.
OG	AZ	XP-000920796 / Applied Optics, March 1998, Vol. 37, No. 7, pages 1243-1248, "Laser-produced lithium plasma as a narrow-band extended ultraviolet radiation source for photoelectron spectroscopy", G. Schriever, et al.

Examiner:

Date: 06/07/05

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

LIST OF PRIOR ART CITED BY APPLICANT
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Docket No. GK-OEH-171 / 500814.20073
 Applicant(s): Max Christian SCHUERMANN, Thomas MISSALLA and Bernd SEHER
 Application No. 10 / 672,110
 Filed: concurrently herewith - September 26, 2003
 Group:
 Examiner:

U.S. PATENT DOCUMENTS

Exam. Init		Document Number	Date	Name	Class	Sub-Class	Filing Date Appropriate
	AA						
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	AG						
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	CLASS	Sub-Class	Translation YES NO
OG	AL	199 48 264	11/08/2001	Germany			Abstract only
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	AN						
	AO						
	AP						
	AQ						
	AR						
	AS						

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	AV	
	AW	
	AX	
	AY	
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Examiner: *Oluf Olu* Date: 06/07/05

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